

October 29, 2003

To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

Fr: George O. Saile Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject:

Divisional Patent Application of
Serial No.: 10/038,389 1/3/02

YING-LANG WANG, SHIH-CHI LIN, YI-LUNG CHENG,
CHI-WEN LIU, MING-HUA YOO, WEN-KUNG CHENG,
JIANN-KWANG WANG

IMPROVED CMP PROCESS LEAVING NO RESIDUAL
OXIDE LAYER OR SLURRY PARTICLES

PRELIMINARY AMENDMENT

Dear Sir:


This is a preliminary amendment for the above referenced Divisional Patent
Application. Please amend the above identified application for patent as follows:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States
Postal Service as first class mail in an envelope addressed to: Commissioner of Patents
and Trademarks, Washington, D.C. 20231, on October 29, 2003.

Stephen B. Ackerman, Reg. No. 37,761

Signature/Date

 10/29/03